Younghee Lee

List of Publications by Year in Descending Order

Source: https://exaly.com/author-pdf/2630313/younghee-lee-publications-by-year.pdf
Version: 2024-04-27

This document has been generated based on the publications and citations recorded by exaly.com. For the latest version of this publication list, visit the link given above.
The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

23 papers	1,038 citations	19 h-index	25 g-index
25 ext. papers	1,181 ext. citations	8 avg, IF	4.95 L-index

#	Paper	IF	Citations
23	Thermal Atomic Layer Etching of Gallium Oxide Using Sequential Exposures of HF and Various Metal Precursors. *Chemistry of Materials*, **2020**, 32, 5937-5948	9.6	8
22	Thermal etching of AlF3 and thermal atomic layer etching of Al2O3. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2020**, 38, 022603	2.9	13
21	Thermal Atomic Layer Etching of Al2O3, HfO2, and ZrO2 Using Sequential Hydrogen Fluoride and Dimethylaluminum Chloride Exposures. *Journal of Physical Chemistry C*, **2019**, 123, 18455-18466	3.8	25
20	In Situ Thermal Atomic Layer Etching for Sub-5 nm InGaAs Multigate MOSFETs. *Nano Letters*, **2019**, 19, 5159-5166	11.5	19
19	First Transistor Demonstration of Thermal Atomic Layer Etching: InGaAs FinFETs with sub-5 nm Fin-width Featuring in situ ALE-ALD **2018**,		17
18	Thermal atomic layer etching of HfO2 using HF for fluorination and TiCl4 for ligand-exchange. *Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films*, **2018**, 36, 061504	2.9	29
17	Coating Solution for High-Voltage Cathode: AlF Atomic Layer Deposition for Freestanding LiCoO Electrodes with High Energy Density and Excellent Flexibility. *ACS Applied Materials & Interfaces*, **2017**, 9, 9614-9619	9.5	47
16	Thermal Atomic Layer Etching of Titanium Nitride Using Sequential, Self-Limiting Reactions: Oxidation to TiO2 and Fluorination to Volatile TiF4. *Chemistry of Materials*, **2017**, 29, 8202-8210	9.6	52
15	Prospects for Thermal Atomic Layer Etching Using Sequential, Self-Limiting Fluorination and Ligand-Exchange Reactions. *ACS Nano*, **2016**, 10, 4889-94	16.7	90
14	Atomic Layer Deposition of Metal Fluorides Using HF Pyridine as the Fluorine Precursor. *Chemistry of Materials*, **2016**, 28, 2022-2032	9.6	44
13	Cross-linked aluminum dioxybenzene coating for stabilization of silicon electrodes. *Nano Energy*, **2016**, 22, 202-210	17.1	24
12	Trimethylaluminum as the Metal Precursor for the Atomic Layer Etching of Al2O3 Using Sequential, Self-Limiting Thermal Reactions. *Chemistry of Materials*, **2016**, 28, 2994-3003	9.6	65
11	Selectivity in Thermal Atomic Layer Etching Using Sequential, Self-Limiting Fluorination and Ligand-Exchange Reactions. *Chemistry of Materials*, **2016**, 28, 7657-7665	9.6	63
10	Mitigating irreversible capacity losses from carbon agents via surface modification. *Journal of Power Sources*, **2015**, 275, 605-611	8.9	12
9	Atomic Layer Deposition of AlF3 Using Trimethylaluminum and Hydrogen Fluoride. *Journal of Physical Chemistry C*, **2015**, 119, 14185-14194	3.8	59
8	Surface-coating regulated lithiation kinetics and degradation in silicon nanowires for lithium ion battery. *ACS Nano*, **2015**, 9, 5559-66	16.7	99
7	Mechanism of Thermal Al2O3 Atomic Layer Etching Using Sequential Reactions with Sn(acac)2 and HF. *Chemistry of Materials*, **2015**, 27, 3648-3657	9.6	50

6	Atomic Layer Etching of HfO2Using Sequential, Self-Limiting Thermal Reactions with Sn(acac)2and HF. *ECS Journal of Solid State Science and Technology*, **2015**, 4, N5013-N5022	2	70
5	Atomic Layer Etching of AlF3 Using Sequential, Self-Limiting Thermal Reactions with Sn(acac)2 and Hydrogen Fluoride. *Journal of Physical Chemistry C*, **2015**, 119, 25385-25393	3.8	31
4	Atomic layer etching of Al2O3 using sequential, self-limiting thermal reactions with Sn(acac)2 and hydrogen fluoride. *ACS Nano*, **2015**, 9, 2061-70	16.7	104
3	Molecular layer deposition of aluminum alkoxide polymer films using trimethylaluminum and glycidol. *Langmuir*, **2011**, 27, 15155-64	4	39
2	Molecular Layer Deposition of Conductive Hybrid Organic-Inorganic Thin Films Using Diethylzinc and Hydroquinone. *ECS Transactions*, **2010**, 33, 191-195	1	30
1	Atomic Layer Deposition of LiOH and Li2CO3 Using Lithium t-Butoxide as the Lithium Source. *ECS Transactions*, **2010**, 33, 223-229	1	47